

In re **Specification** of: Eugene P. Marsh

Serial No.: 10/848,985

Filed: May 18, 2004

For: SURFACE TREATMENT OF AN OXIDE LAYER TO ENHANCE ADHESION OF A RUTHENIUM METAL LAYER

Group Art Unit: 2818

Examiner: H. Jey Tsai

Atty. Docket: 2002-0717.01/US

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Certificate of Mailing (37 CFR §1.8)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to:
Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on the date below:

May 5, 2006

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Date

Signature

INFORMATION DISCLOSURE STATEMENT

In compliance with the duty of disclosure under 37 C.F.R. § 1.56, Applicants respectfully request that this Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. As the references include printed copies of web pages, copies of the references are included herewith.

In accordance with 37 C.F.R. § 1.97(g), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 C.F.R. § 1.56(a) exists.

The following references are cited for the Examiner's review:

Web Pages

Power Chemical Corp., product information at www.powerchemical.net/coupling.htm; date unknown, printed April, 2006.

Mitsubishi International Corp., product information at www.micchem.com/products/SilaneCouplingAgents.htm; date unknown, printed April, 2006.

Semiconfareast, technical information at www.semiconfareast.com/polysilicon-deposition.htm; date unknown, printed April, 2006.

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As this information is being submitted within three months of the date of filing of the application, Applicant understands that no fee or certification is required for the submission and consideration of this information at this time.

If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicant's undersigned attorney at the number indicated.

* * * *

A Form PTO-1449 is enclosed herewith.

Respectfully submitted,

Agent for Applicant

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INFORMATION DISCLOSURE STATEMENT BY APPL					Applicant:			
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EXAMINER:

Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.